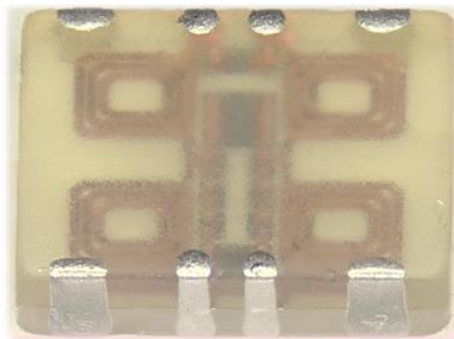


CMSE 2025

Integrated Thin Film Passive Components:

A New Option for Miniature Flight
Electronics



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Outline

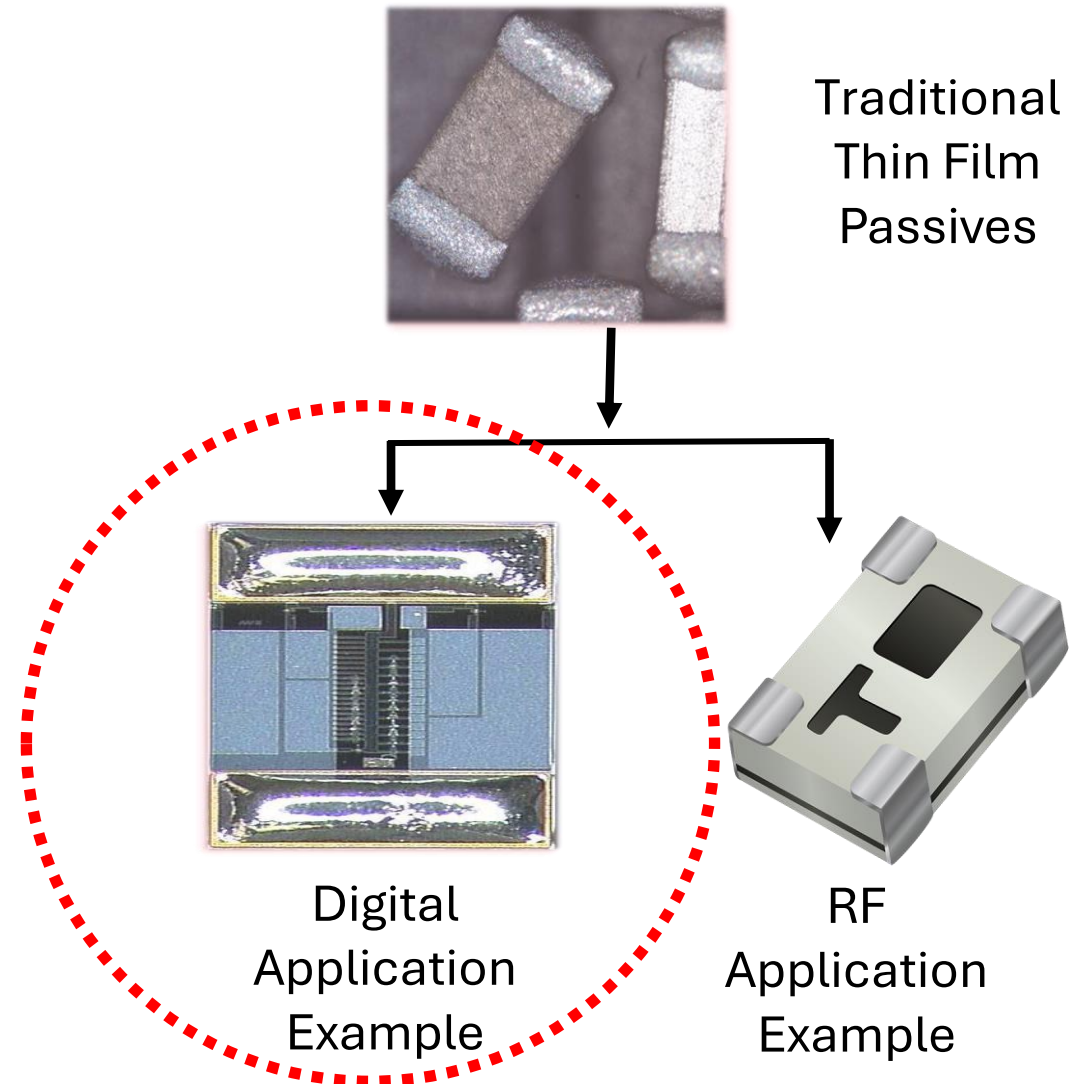
Thin Film passives components advantages:

- Size
- Weight
- Stable & repeatable electrical response

Review the state of **integrated** Thin film options:

Document & Discuss current state of the art integration

Summary

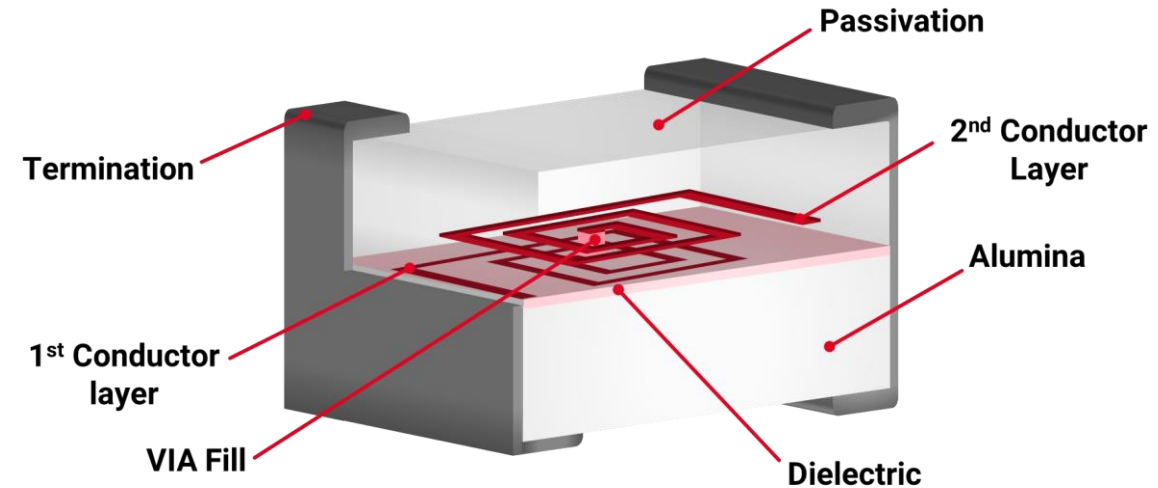


Thin Film Structures

- » **Ultra Tight Tolerances** Capacitors
- » **Ultra Tight Tolerance** Inductors
- » **High directivity Miniature size** Directional Couplers
- » **Wide Band** Couplers
- » **Smallest 3dB 90°** Couplers

- » **High-Power** Band-Pass Filters
- » **High Power** Low Pass Filters
- » **High Power** High Pass Filters
- » **Industry's Lowest Current Ratings** Fuses
- » **High Frequency (> 20Ghz)** Strip Line Couplers and Band Pass Filters

StructureS Advanced from simple plates to:



How did we get here: Thin Film Technology

Thin-Film production is unlike MLCC wet or dry processes

Class 1000 clean rooms, with class 100 laminar-flow hood work areas

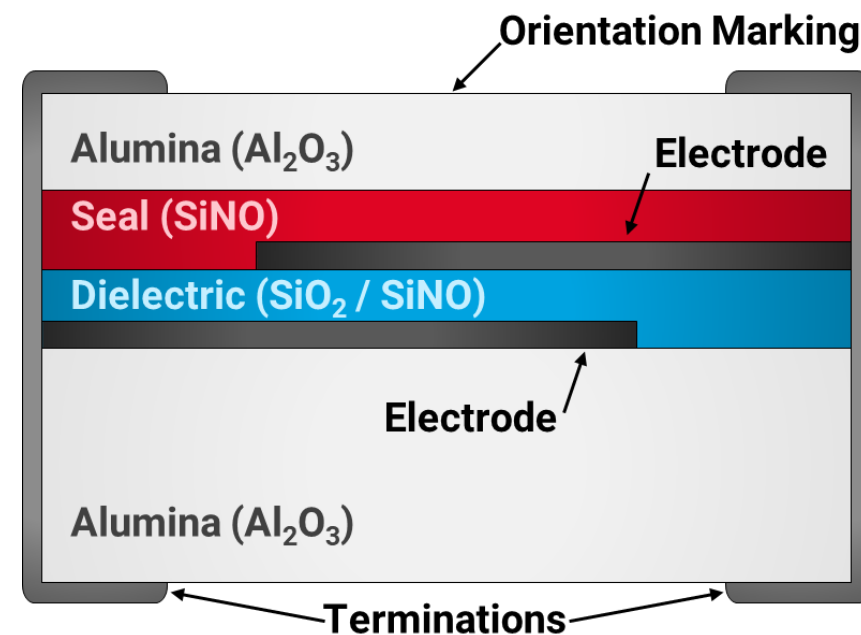
High vacuum metal deposition systems for high-purity electrode construction

Photolithography equipment for line definition down to $2.0\mu\text{m}$ accuracy

Plasma-enhanced CVD for various dielectric depositions

High accuracy, microprocessor-controlled dicing saws for chip separation

High speed, high accuracy sorting to ensure strict tolerance adherence.



Thin Film Discrete Capacitors

State of technology:

Super repeatable RF parameters at working frequency

Sizes: 0201 / 0402 / 0603 / 0805

Ultra **Tight Tolerances**: $\pm 0.01\text{pF}$ (Z), $\pm 0.02\text{pF}$ (P), $\pm 0.03\text{pF}$ (Q)

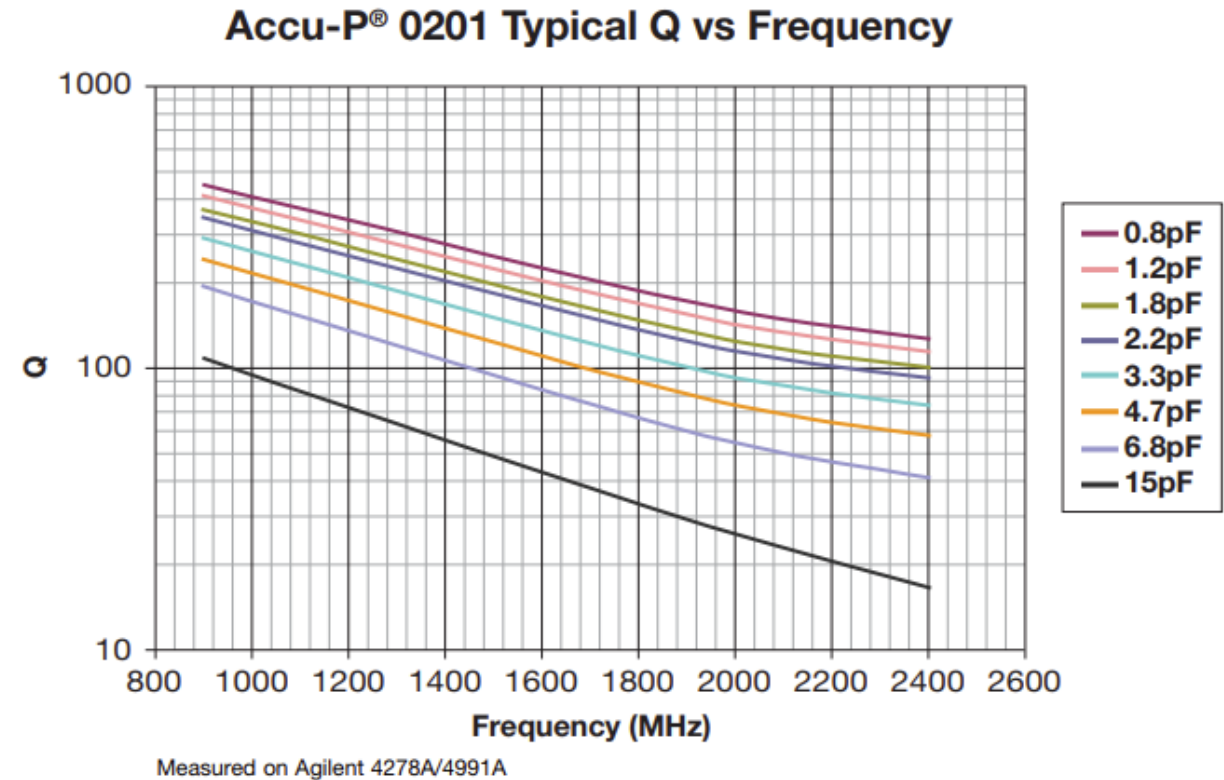
Capacitance Values Start as Low as **0.05pF**

Intermediate capacitance values

High **Q** / Low **ESR**

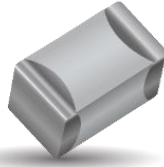
Meets or exceeds the requirements of AEC-Q200-3

0201	0402	0603	0805	1210
0.05 - 22 pF	0.05 - 68 pF	0.05 - 39 pF	0.1 - 68 pF	0.1 - 47 pF



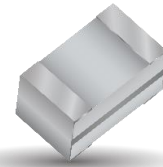
Discrete Capacitor Electrical Advantage

3.3pF MLC

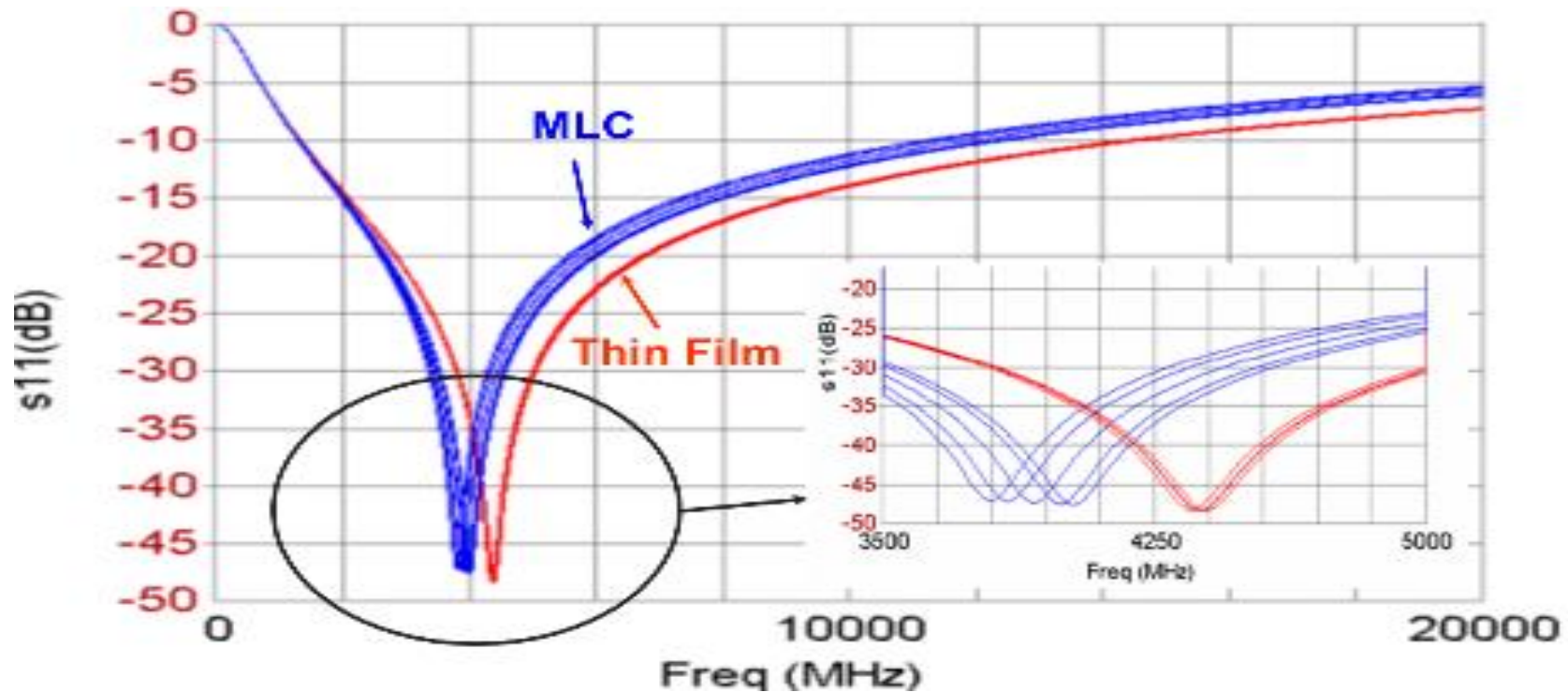


VS

3.3pF Thin Film



Repeatable RF Performance



Thin Film Discrete Inductors

State of technology:

Sizes: 0201 / 0402 / 0603 / 0805

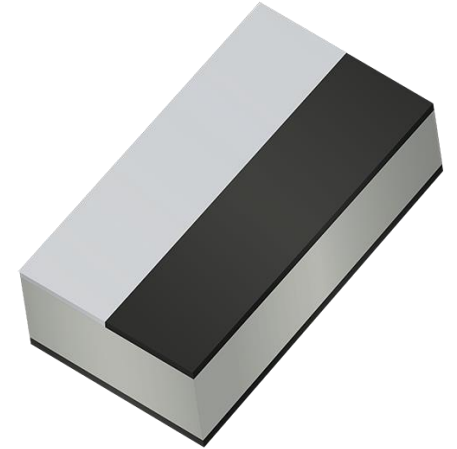
Ultra Tight Tolerances **A**($\pm 0.05\text{nH}$), **B**($\pm 0.1\text{nH}$), **C**($\pm 0.2\text{nH}$), **F**(1%) and **G**(2%)

High **Q** Factor and High SRF

High Power Dissipation

Repeatable Performance at High Frequencies

Meets or exceeds the requirements of AEC-Q200-3



	Accu-L	AL	AS	LCWC	LCCI
Type	Thin Film	Air Core	Air Core	Wire Wound Chip	Multi-Layer Ceramic
Temperature	-55°C To +125°C	-40°C To +125°C	-40°C To +125°C	-40°C To +125°C	-40°C To +85°C
Size	0201, 0402, 0603, 0805	0605, 1212, 1516, 2523	0806, 0807, 0908	0402, 0603, 0805, 1008, 1210, 1812	0201, 0402, 0603
SRF	1.4 - 35 GHz	0.49 - 12.5 GHz	2.5 - 5.2 GHz	0.14 - 12500 GHz	0.4 - 10 GHz
DCR	0.04 - 1 Ω	0.0011 - 0.09 Ω	0.0034 - 0.01 Ω	0.03 - 3350 Ω	0.05 - 3.2 Ω
Inductance	0.33 - 22 nH	1.65 - 538 nH	5.5 - 27.3 nH	1 - 15000 nH	0.3 - 270 nH
Q	7 - 60	87 - 145	60 - 130	15 - 80	4 - 12
Current	150 - 2000 mA _(IDC)	1.5 - 4 A _(Ir)	2.7 - 4.4 A _(Ir)	Size: 0402 - 1008 30 - 1360 mA _(IDC) Size: 1210 - 1812 150 - 1500 mA _(Irms)	120 - 1000 mA _(Irms)

Technology to combine:

Typical Substrate Properties

Nominal (Typical) Properties	Al ₂ O ₃ 99.6%	Al ₂ O ₃ 96.0%	Fused Silica	BeO 99.5%	AlN	Glass Borosilicate	P- Silicon Boron Doped	N++ Silicon Arsenic
Loss Tangent @ 10 GHz	0.0002	0.0002	0.0001	0.0003	0.001	0.003	N/A	N/A
Thermal Conductivity (W/mK)	25.5	24.7	1.38	280	170	1.16	150	150

Resistor Technology

Thin Film Resistors

SiCr

TaN

Typical Sheet Resistivity (ohm/sq)

500-1300

10-100

TCR (ppm/°C -25 to 125°C)

±50; ±100; ±250

-100 to -150

Min Tolerance (Corresponding Greater Value)

0.5% or 0.1Ω

0.5% or 0.1Ω

Capacitor Materials Typical Values

Material

SiN

SiON

SiO₂

BCB

PI

Range

1-500pF

1-500pF

1-500pF

1-50pF

0.5-10pF

Tolerance
Value Dependent

±5%

±5%

±5%

±20%

±20%

Stability (TCC)

±60 ppm/°C

±60 ppm/°C

±30 ppm/°C

±42 ppm/°C

±100 ppm/°C

BDV (v/μm)

300

600

1000

300

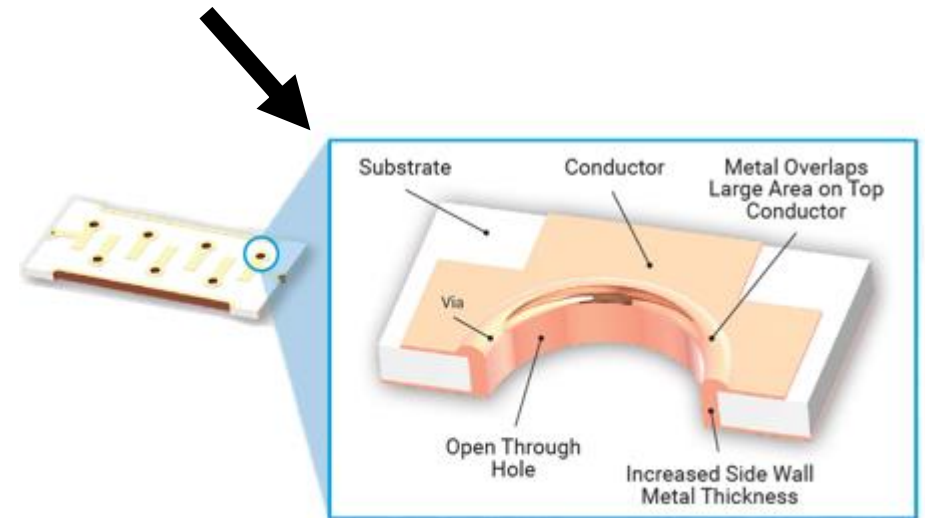
200

Technology to combine:

Metal	Thickness (μm)	
	Min	Max
TaN (Resistive)	0.03	0.15
SiCr (Resistive)	0.03	0.15
TiW	0.03	0.15
Cr	0.03	0.15
NiV	0.1	0.75
Al	0.1	1
	1	2.5
Au	0.1	1
	1	5
Cu	1	2.5
	0.5	1
Plated Ni	1	4
	0.75	1
Plated Au	1	15
	2.5	50
Plated Metal Stack	-	75
Line Width: Plated Thickness Ratio	N/A	N/A

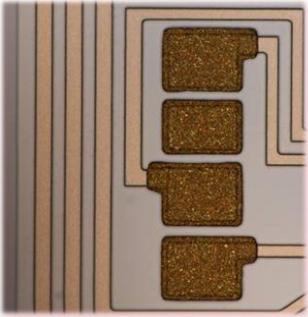
+

VIAs	
Vias	Min
Via Diameter (D)	125 μm
Via Aspect Ratio (D:T)	0.6:1
Via Spacing (Center to Center)	150 μm + D
Pad Size Around Via	150 μm + D
Circumference to Edge Distance	T
Via Center	-
Substrates Available	-



Termination Styles

Au Wire-bond



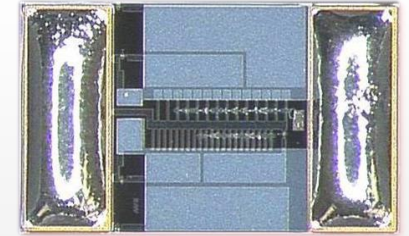
Surface Mount
(single I/O pair)



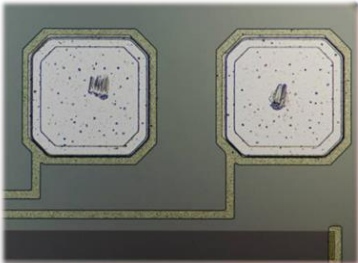
Castellated Via
(AlN, Alumina, and BeO)



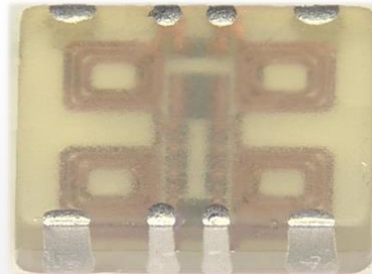
Land Grid Array



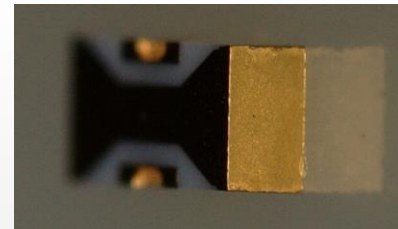
Al Wire-bond



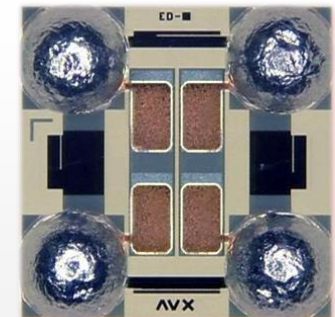
Surface Mount
(Striped, multiple I/Os)



Edge Wrap



Ball Grid Array



Design Considerations

Substrates Options

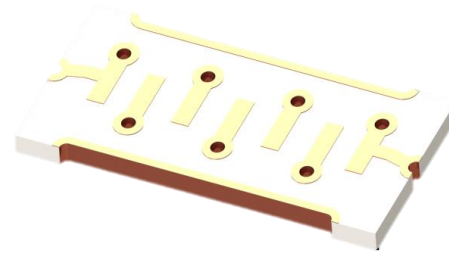
- Aluminum Nitride (AlN)
- Alumina (Al_2O_3)
- Silicon
- Glass
- Quartz
- Beryllium Oxide (BeO)

Dielectric Materials

- Silicon Oxynitride (SiON)
- Silica SiO_2
- Benzo cyclobutene (BCB)
- Polyimide (PI)

Sputtered & Plated Metals Options

- Gold
- Copper
- Aluminum
- Nickel



Conductor Metal Stack

TiW – Adhesion layer

Copper Conductor Layer $\sim 8\mu\text{m}$

Nickel Layer $\sim 1\mu\text{m}$

Gold Layer $\sim 1\mu\text{m}$

- Thicker gold is required for wirebonding

Resistive Materials

- SiCr
- TaN

Solder Barrier Options

Exposed Nickel on Conductor Metal Stack

- Oxidation creates natural solder barrier
- $50\mu\text{m}$ length minimum required
 - Width follows Conductor rules

Dielectric Material as Solder Barrier



Lumped Elements Integrated on Chip

- Inductors, Capacitors, and Resistors

External Components Attached

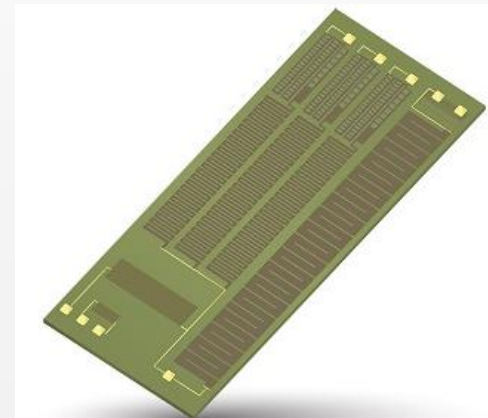
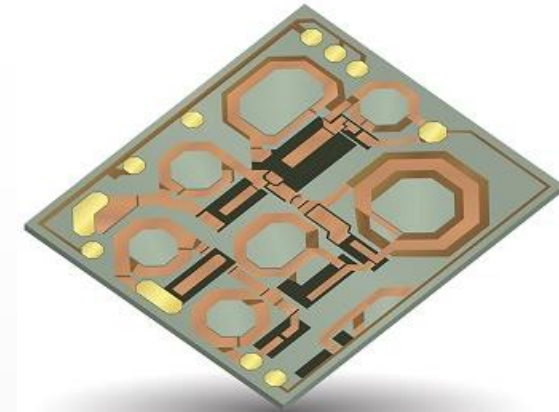
- Solderable pads or Wirebondable attachments

Vias

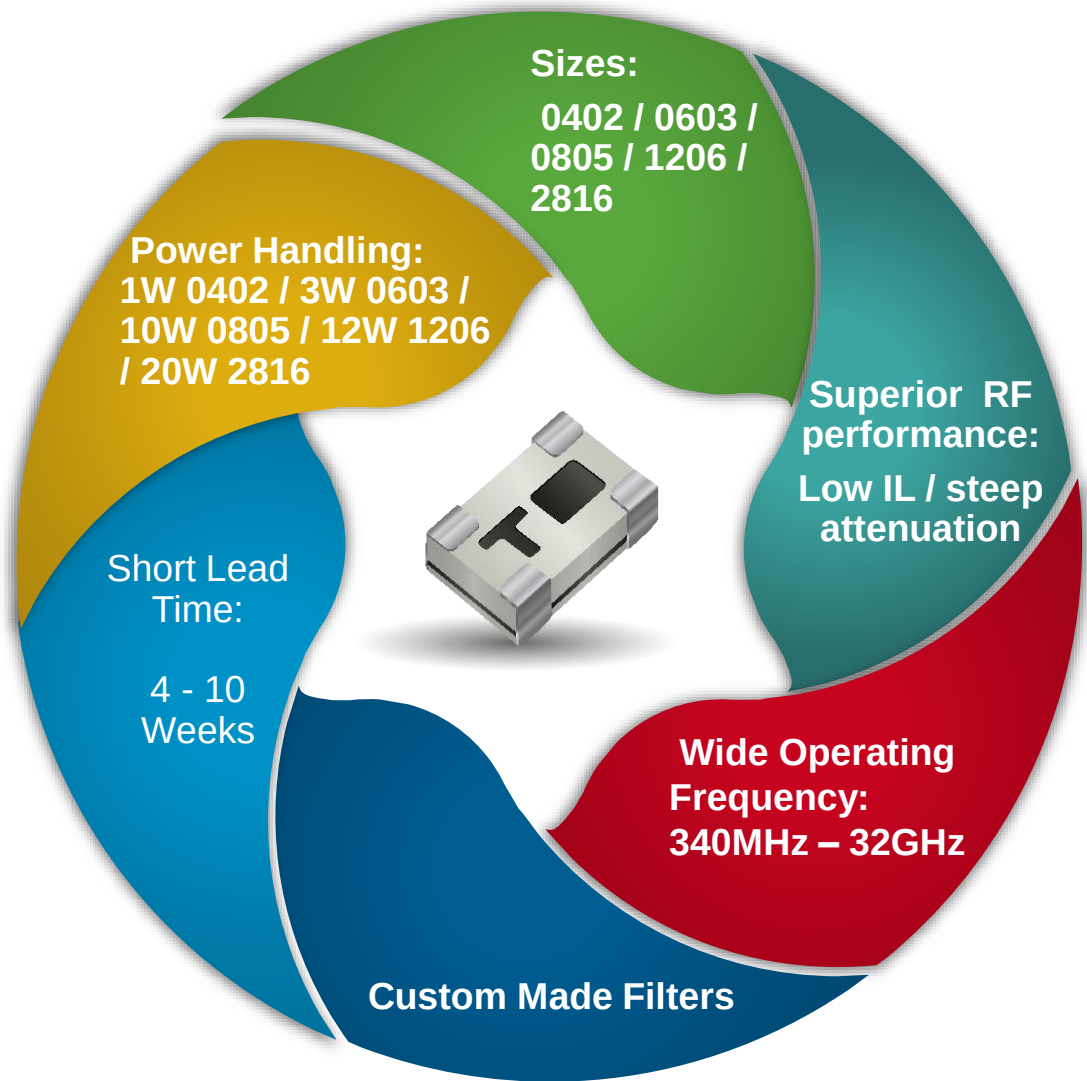
- Front and Backside processing (AlN, Alumina, BeO)

Savings

- Fewer components
 - Reduces weight
 - Reduces work and rework time
- Improves component matching
- Decrease size
 - X and Y dimensions reduced by component stacking
 - Z dimension could grow, but thin materials available



Outcome 2: High Power RF Devices



Benefits:

- No performance variance with temperature changes
- High power rating in small form factor
- High part-to-part and lot-to-lot repeatability
- Miniature size
- Short lead time – non LTCC process

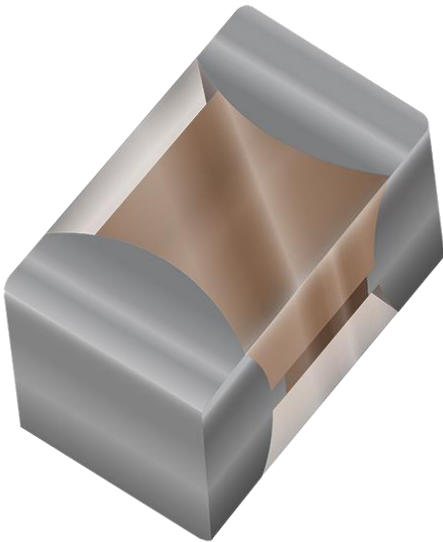
	0402	0603	0805	1206	2816
Dimensions (mm)	1 x 0.58	1.6 x 0.84	2.03 x 1.55	3.1 x 1.6	7 x 4
Weight (mg)	1	1.73	10.8	15.57	131

Outcome 3: High Density Passive



Example 1:

Die size: 6.386 x 5.572 mm
Thickness: 127 μ m
27 resistors (resistors occupy 15% of the die space)
Weight ~ 12 mg

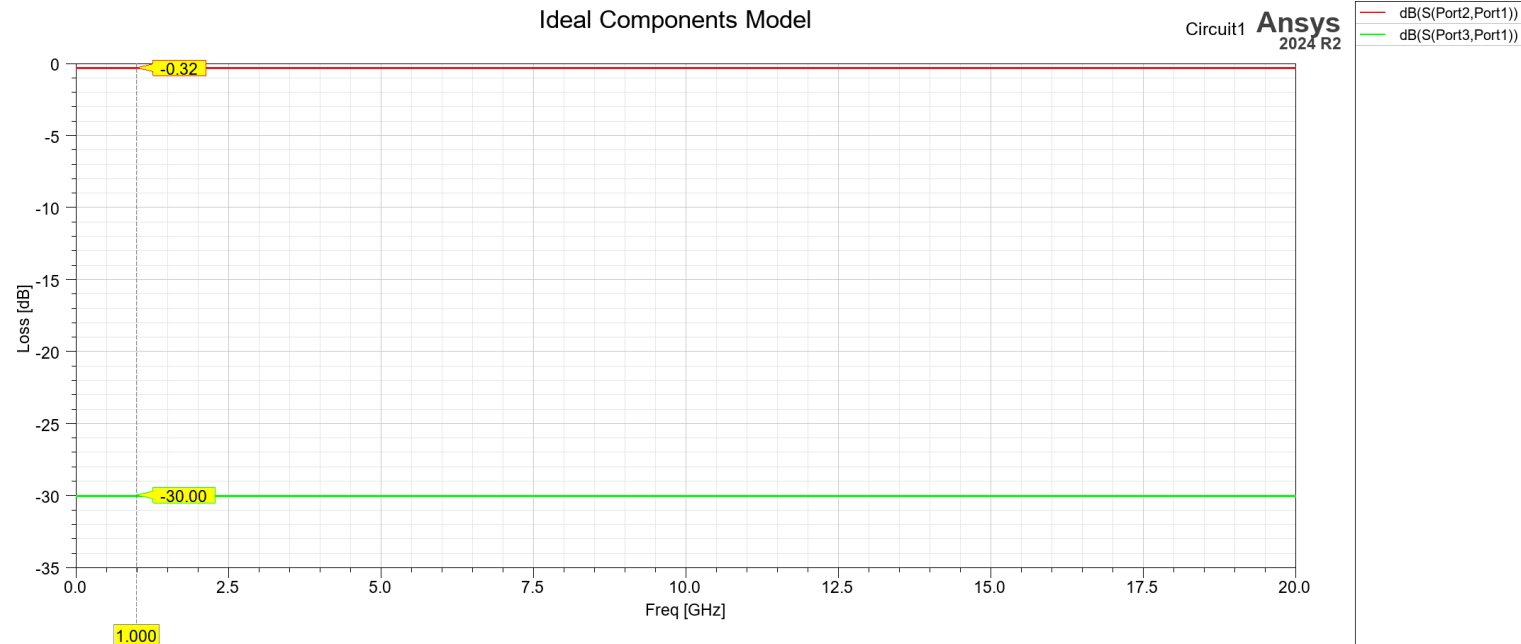
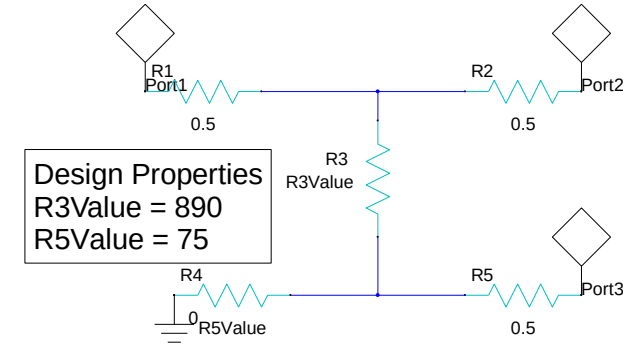


High Density Passive	Equivalent Discrete part
27 resistors in 1 package	27 discrete resistor
~ 5.32 mm ² in optimized design	Board area 8 mm ² <u>plus routing</u>
127 μ m	230 μ m
~ 3 mg in optimized design	~ 6 mg

Real World Design Comparison Custom Resistor Divider

Ideal Circuit

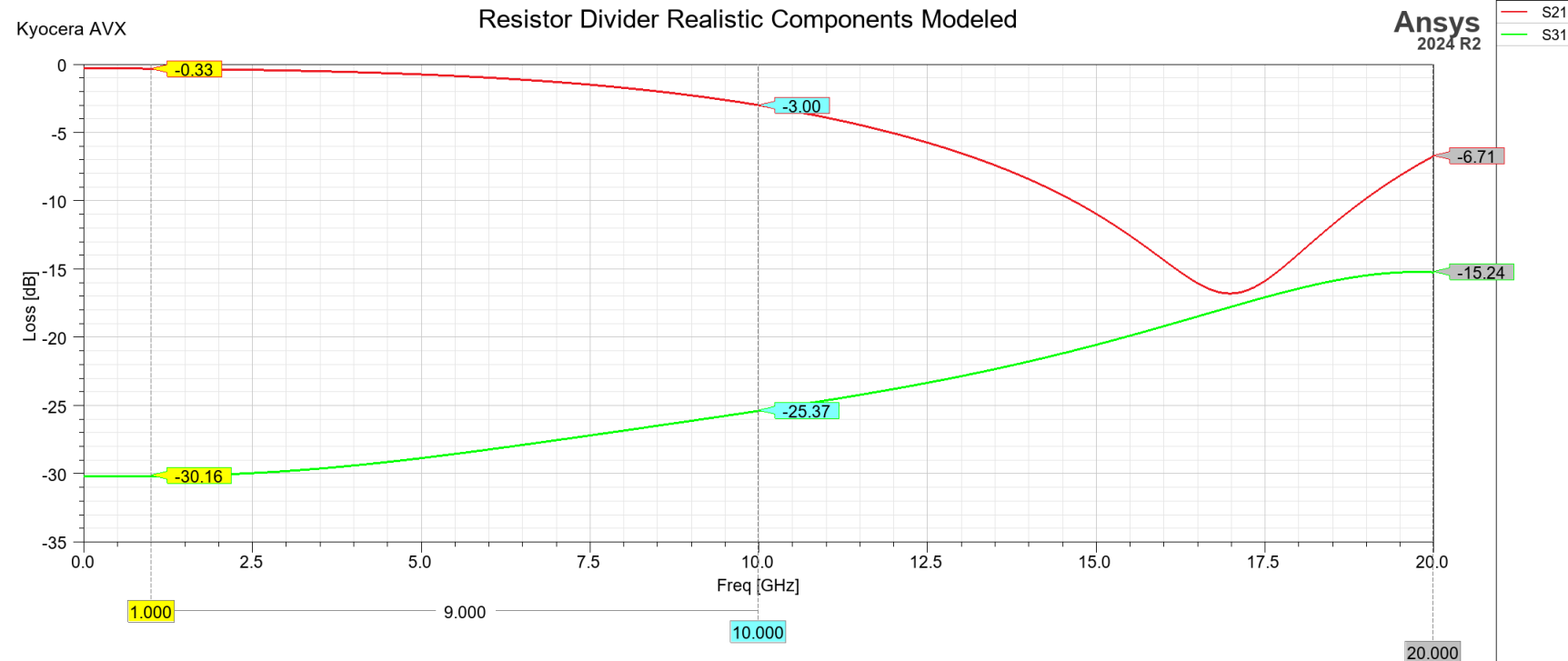
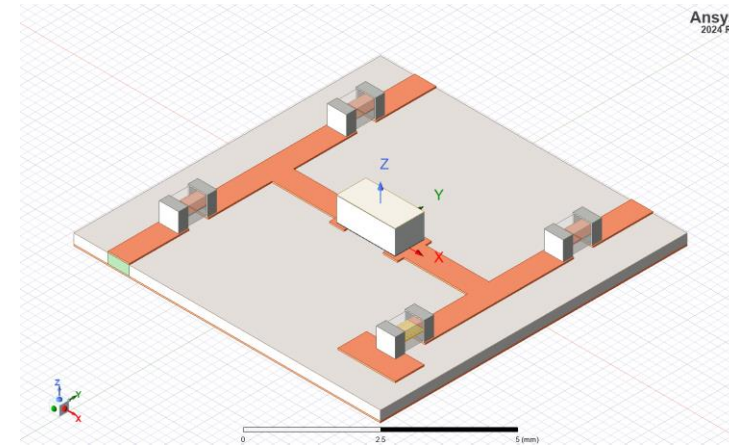
- Looking at a design for a 30dB resistor divider
- R3 needs to dissipate enough power to handle the 30dB drop
 - Estimated 500mW rating required
- Estimated ideal circuit shown



Real World Design Comparison Custom Resistor Divider

COTS Components and Equivalents

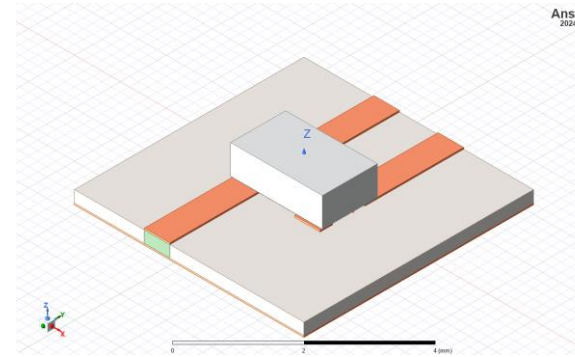
- Model uses COTS components
 - 0.5ohm resistors based on Kyocera-AVX UBR style design
 - Generic resistor with 0.5 ohm resistance
 - 75 ohm resistor is Kyocera-AVX UBR design
 - This is a COTS broadband component
 - 890 ohm resistor is based on Kyocera-AVX CR style design
 - Power handling exceeded UBR style's capability
 - 0603 style flip chip resistor with AlN was used
 - Power rating would exceed 500mW
- Model shows 30dB attenuation at 1GHz, and 25dB attenuation at 10GHz



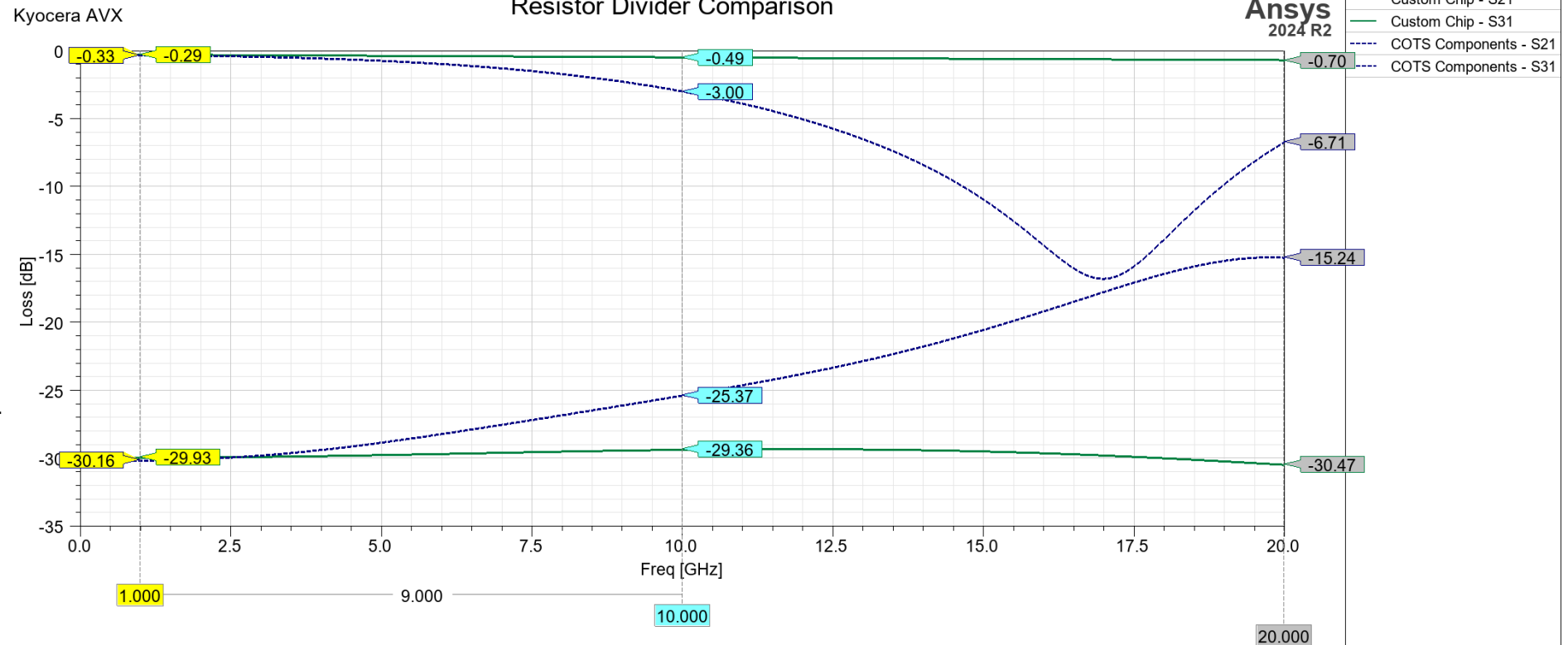
Real World Design Comparison Custom Resistor Divider

Custom Chip Design

- Single chip with all 5 resistors included
- Reduces parasitics by including in 1 chip
- RF Performance extended through 20 GHz
- Size of chip for simulation is 0805
- Flip chip style component
- Preliminary design
 - Needs to be verified with production
 - Could be modified based on customer requirements
- COTS parts – Dash line – Blue
- Custom Chip – Solid Line – Green



Resistor Divider Comparison



Summary

Thin Film integration technology advantages:

- Past discrete part design created highly efficient complex structures
- Integrated designs are quickly created by large simulation data base
- Broad material options exist for integrated designs
- Integration can take the form of RF Interposer or 'Digital' structures
- Substrate and component options exist
- Thin film line and oxide accuracies enable low loss, tight response
- Smaller, lighter structures with better electrical response are created